

Paper List

January –December, 2025

- [E2025-1\(F\)](#) Contamination Behavior of Bare Silicon Wafer Surface During Single-Wafer Process Using Deionized Water Containing Ultra-Trace Metal Impurities
ECS Journal of Solid State Science and Technology, Vol.14, No.5, (2025), pp.054008
K. Tsutano, T. Mawaki, Y. Shirai and R. Kuroda
<https://iopscience.iop.org/article/10.1149/2162-8777/add809>
DOI: 10.1149/2162-8777/add809
- [E2025-2\(C\)](#) On the determination threshold of illumination-adaptive signal selection technology for multi-stage LOFIC CMOS image sensors
2025 International Image Sensor Workshop (IISW2025), pp.61-64, R02.5, June 2, (2025), Hyogo
Yoshihito Hirai, Kohei Takizawa, Takezo Mawaki, Rihito Kuroda
DOI: <https://doi.org/10.60928/wjde-as5j>
- E2025-3(F) Metal Contamination Behavior on Silicon Dioxide Surface Rinsed With Deionized Water Containing Ultra-Trace Metal During Single-Wafer Cleaning
IEEE Transactions on Semiconductor Manufacturing, Vol.38, No.3, (2025), pp.492-498
K. Tsutano, T. Mawaki, Y. Shirai, R. Kuroda
DOI: [10.1109/TSM.2025.3575743](https://doi.org/10.1109/TSM.2025.3575743)
- [E2025-4\(C\)](#) [Invited paper]
Development of Transparent Flexible Micro-LED Display with High-Precision Mass-Transfer Technology
SID Symposium Digest of Technical Papers, Vol.56. Issue 1, pp. 793 – 796, 59-2
Kengo Shima, Tatsuya Ishida, Kazuya Adachi, Koichi Kajiyama, Yasuyuki Shirai, Takahiro Ishinabe
DOI: 10.1002/sdtp.18287
- [E2025-5\(F\)](#) Statistical measurement technology for capacitance and leakage current characteristics of integrated devices
Japanese Journal of Applied Physics, Vol.64, No.9, (2025), pp.091005
Koga Saito, Ryoya Nishimaki, Takezo Mawaki and Rihito Kuroda
<https://iopscience.iop.org/article/10.35848/1347-4065/ae0224>
DOI: 10.35848/1347-4065/ae0224

- [E2025-6\(C\)](#) Statistical Capacitance Measurement of Si Trench Capacitors Using Array Test Circuit
Extended Abstracts of the 2025 International Conference on Solid State Devices and Materials (SSDM2025), pp.165-166, C-1-03, September 16, (2025), Yokohama
Ryoya Nishimaki, Koga Saito, Takezo Mawaki, Ken Miyauchi, Rihito Kuroda
- [E2025-7\(C\)](#) [Invited] [Best Paper Award]
Progress in Development of Advanced High Dynamic Range CMOS Image Sensors
PROCEEDINGS OF THE INTERNATIONAL DISPLAY WORKSHOPS, VOL. 32, 2025 (IDW '25), pp. 1612-1615 (IST1-1) December 4, Hiroshima
Ken Miyauchi
<https://www.idw.or.jp/finalprogram.html#IST1>
- [E2025-8\(C\)](#) A 120 dB Dynamic Range 3D Stacked 2-Stage LOFIC CMOS Image Sensor with Illuminance-Adaptive Signal Selection Function
71st Annual IEEE International Electron Devices Meeting (IEDM2025), 42-2, December 10, (2025), San Francisco, US
Kohei Takizawa, Yoshihito Hirai, Masaya Yoshida, Takezo Mawaki, Ken Miyauchi, Rihito Kuroda
DOI: [10.1109/IEDM50572.2025.11353535](https://doi.org/10.1109/IEDM50572.2025.11353535)
- [E2025-9\(C\)](#) A Global Shutter Burst CMOS Image Sensor with 6-Tpixel/s Readout Speed, 256-recording Frames and -170dB Parasitic Light Sensitivity
71st Annual IEEE International Electron Devices Meeting (IEDM2025), 42-5, December 10, (2025), San Francisco, US
Masuto Kitamura, Yasunori Kawaguchi, Naoya Kuriyama, Tomoaki Maeda, Toshifumi Imamura, Takezo Mawaki, Shigetoshi Sugawa, Rihito Kuroda
DOI: [10.1109/IEDM50572.2025.11353722](https://doi.org/10.1109/IEDM50572.2025.11353722)